

L Number	Hits	Search Text	DB	Time stamp
1	2050	(gas\$4 or outgas\$4) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:04
2	278	((gas\$4 or outgas\$4) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)) and ((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:06
3	160	((gas\$4 or outgas\$4) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)) and ((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1))) and ((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:06
4	103	((((gas\$4 or outgas\$4) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)) and ((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1))) and ((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1))) and ((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1))) and vacuum	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:07
5	65	((((gas\$4 or outgas\$4) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)) and ((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1))) and ((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1))) and ((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1))) and vacuum) and ((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)) same vacuum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:08

6	9	<p>((((gas\$4 or outgas\$4) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1))) and vacuum) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)) same vacuum)) and 250/\$.ccls.</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:14
8	56	<p>((((gas\$4 or outgas\$4) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1))) and vacuum) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)) same vacuum)) not (((((((gas\$4 or outgas\$4) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1))) and vacuum) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)) same vacuum)) and 250/\$.ccls.)</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:14

11	43	(((((((gas\$4 or outgas\$4) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1))) and vacuum) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4)) same (((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)) same vacuum)) not ((((((gas\$4 or outgas\$4) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4)) same (((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1))) and vacuum) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4)) same (((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)) same vacuum)) and 250/\$.ccls.)) and chamber\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:15
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13	43	(((((((gas\$4 or outgas\$4) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)) same vacuum)) and vacuum) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)) same vacuum)) not ((((((gas\$4 or outgas\$4) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1)) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same (irradiat\$4 or radiat\$4 or exposur\$4) same (electron\$1 near3 beam) same (film\$1 or substrate\$1 or wafer\$1))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4 or collect\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)))) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1))) and vacuum) and (((gas\$4 or outgas\$4) with (releas\$4 or produc\$4 or creat\$4)) same ((irradiat\$4 or radiat\$4 or exposur\$4) with (electron\$1 adj beam) with (film\$1 or substrate\$1 or wafer\$1)) same vacuum)) and 250/\$.ccls.)) and chamber\$1) and (vacuum with (chamber\$1 or hous\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/08 15:19
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